			- m
	Application No.	Applicant(s)	ļot v s
AL /* CAR L ***	09/881,408	AHN ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Thao X Le	2814	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.			
1. This communication is responsive to <u>03/17/04</u> .			
2. The allowed claim(s) is/are <u>1-31,52 and 54-59</u> .			
3. \boxtimes The drawings filed on <u>13 June 2001</u> are accepted by the E	xaminer.		
 4. ☐ Acknowledgment is made of a claim for foreign priority ur a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	e been received. e been received in Application No.		ation from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		ly complying with the re	equirements
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			NOTICE OF
6. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached			
1) 🔲 hereto or 2) 🔲 to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on the dra he header according to 37 CFR 1.12	wings in the front (not th 21(d).	ne back) of
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT	SIT OF BIOLOGICAL MATERIAL FOR THE DEPOSIT OF BIOLOG	L must be submitted. ICAL MATERIAL.	Note the
A44			· :
Attachment(s) 1. Notice of References Cited (PTO-892)	5. Notice of Informa	l Patent Application (P	ГО-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summa		
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0	Paper No./Mail [08), 7. ☐ Examiner's Amer	Date ndment/Comment	`
Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit	8. 🛛 Examiner's State	ment of Reasons for Al	lowance
of Biological Material	9. 🗍 Other		

Application/Control Number: 09/881,408 Page 2

Art Unit: 2814

REASONS FOR ALLOWANCE

1. The following is an examiner's statement of reasons for allowance: Claims 1, 20, 52, 54, and 55 are allowed

- a. With respect to claims 1, 2, 6-31, 52, 54, and 55, the Applicant's reply on 02/19/04 in page 4 first paragraph has overcome the rejections of base claims 1, 20, 52 and 54. The prior art of record fails to discloses all the limitations of the base claim 1, 20, 52, 54, and 55 including the first metal-containing dielectric layer consisting of metal oxide having at least one element selected from Group IVB of the periodic table, and a second metal-containing dielectric layer consisting of metal oxide in contact with the first metal-containing dielectric layer and having at least one element selected from group IIIB of the periodic table.
- b. With respect to claim 3-5, the prior art of record fails to disclose all the limitation of the base claim 3 including heating the metal layer and layer of silicon dioxide to a temperature of from 200°C to less than 400°C and combing metal of the metal layer with oxygen of the silicon oxide to form a metal oxide dielectric material having at least one element selected from Group IVB of the periodic table, and a second metal-containing dielectric layer consisting of metal oxide in contact with the first metal-containing dielectric layer and having at least one element selected from group IIIB of the periodic table.
- c. With respect to claims 56-59, the prior art fails to disclose all the limitations of the base claims 56 and 59 including exposing the hafnium-containing layer and the

Application/Control Number: 09/881,408

Art Unit: 2814

Page 3

lanthanum-containing layer to an oxygen comprising atmosphere by ion bombardment using an energy of about 10 ev or less.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thao X Le whose telephone number is (571) 272-1708. The examiner can normally be reached on M-F from 8:00 AM - 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael M Fahmy can be reached on (571) 272 -1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Thao X. Le 12 Apr. 2004

> LONG PHAM PRIMARY EXAMINER